# Kraig J. Andrews

(248) 798-9388 • kraigandrews1992@gmail.com

### **Education**

• Wayne State University Detroit, MI 2014 – Present Ph.D. Physics

Detroit, MI • Wayne State University M.Sc. Physics 2017

• Michigan State University East Lansing, MI B.Sc. Physics 2014

• Michigan State University East Lansing, MI B.Sc. Astrophysics

### Experience

# • Nano Fabrication & Electron Transport Laboratory

Wayne State University, Detroit, MI

Graduate Research Assistant 2015 – Present

- Fabricate field-effect transistors using two-dimensional semiconductors to invesitgate their intrinsic transport properties.
- Develop novel techniques for making low-resistance Ohmic contacts to a wide variety of two-dimensional semiconductors.

### • National Institute of Materials Science

Tsukuba, Ibaraki Prefecture, Japan

Visiting Graduate Researcher, Summer Intern

- Investigate methods for surface modification of two-dimensional semiconductors for the use of creating a new low-resistance Ohmic contact strategy.

## Interational Course on Computational Physics Undergraduate Researcher

Delft, The Netherlands & East Lansing, MI

2014

- A Joint collaboration with Technische Universiteit Delft and Michigan State University involving the development of computational models of various physical systems to model interactions of materials and optimize employed techniques.

# • Jenoptik Laser Technologies

Brighton, MI 2013

Summer Intern

- Contributed in development of a user interface for laser welding machine that allows user manipulation of robotic end-arm tooling.

- Incorporated microcontroller program via interfaced electronic devices and several developed algorithms to analyze physical data and feedback in real-time.

### **Selected Publications**

- 1. "High Performance WSe<sub>2</sub> Phototransistors with 2D/2D Ohmic Contacts." Tianjiao Wang, Kraig Andrews, Arthur Bowman, Tu Hong, Michael Koehler, Jiaqiang Yan, David Mandrus, Zhixian Zhou, and Ya-Qiong Xu. Nano Letters (xx)xx. 2018.
- 2. ""
- 3. ""

### **Selected Presentations**

1. "Palladium Diselenide as a New Two-Dimensional Electronic Material Beyond Silicon." Kraig Andrews, Arthur Bowman, Upendra Rijal, Amanda Haglund, David Mandrus, and Zhixian Zhou. Society of Vacuum Coaters TechCon, Orlando, FL. May 2018.

- 2. "Improved On-Off in Ratio Black Phosphorus Field-Effect Transistors with True Ohmic Contacts." Kraig Andrews, Arthur Bowman, Upendra Rijal, Michael Koehler, David Mandrus, and Zhixian Zhou. APS March Meeting, Los Angeles, CA. March 2018.
- 3. "High Mobility Palladium Diselenide Field-Effect Transistors Using Heaving n—Doped Graphene Contacts." Arthur Bowman, **Kraig Andrews**, Upendra Rijal, Amanda Haglund, David Mandrus, and Zhixian Zhou. APS March Meeting, Los Angeles, CA. March 2018.
- 4. "Measuring the Barrier Height at Transition Metal Dichalcogenide Heterojunctions." Upendra Rijal, Arthur Bowman, Kraig Andrews, Michael Koehler, David Mandrus, and Zhixian Zhou. APS March Meeting, Los Angeles, CA. March 2018.
- 5. "High-Performance Top-Gated WSe<sub>2</sub> Transistors with Two-Dimensional Ohmic Contacts." **Kraig Andrews**, Upendra Rijal, Arthur Bowman, Hsun-Jen Chuang, Sagar Paduel, Michael Koehler, David Mandrus, and Zhixian Zhou. 41<sup>st</sup> Annual Symposium American Vacuum Society- Michigan Chapter, Ann Arbor, MI. May 2017.
- 6. "Substrate Dependence of Hall and Field-Effect Mobilities in Few-Layer MoS<sub>2</sub> Field-Effect Transistors." Bhim Chamlagain, Perera Meeghage, Hsun-Jen Chuang, Arthur Bowman, Upendra Rijal, **Kraig Andrews**, Joseph Klesko, Charles Winter, and Zhixian Zhou. APS March Meeting, Boston, MA, March 2016.

### **Teaching Experience**

Teaching Assistant, Wayne State University Teaching Assistant, Michigan State University Autumn 2014 – Winter 2018 Winter 2012 – Winter 2014

### **Core Technical Skills**

**Nanofabrication:** Atomic force microscopy (AFM), Electron beam lithography, Photolithography, Scanning electron microscopy (SEM), General clean room abilities (> 1000 hours), Physical vapor deposition (PVD), Electron beam deposition, Plasma etching, Reactive ion etching (RIE)

Languages & Software: C++, Fortran, Java, JavaScript, Languages & Software: C++, Fortran, Java, Languages & Software: C++, Fortran, Languages & Softwa

Operating Systems: OS X, Linux OS, Microsoft Windows